

Annealing studies on ATLAS12 sensors

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Leena Diehl, Riccardo Mori, Marc Hauser, Ines
Messmer, Ulrich Parzefall, Karl Jakobs



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- **Aims:**
 - Quality assurance and test of the sensors provided by the ATLAS Strip Collaboration for the Upgrade of the ATLAS Experiment:
 - Full characterization of the sensor performance with the other groups, we focus on the annealing behaviour through charge collection, leakage current and impedance (capacitance) measurements.
 - Difference between room temperature and 60°C annealing in p-type sensors:
 - So far, mainly 60°C studies have been carried out.
 - In the near future: impedance spectroscopy in irradiated sensors:
 - Hints about main defects behaviour (controlling the lifetime) vs. Annealing.

- Materials:

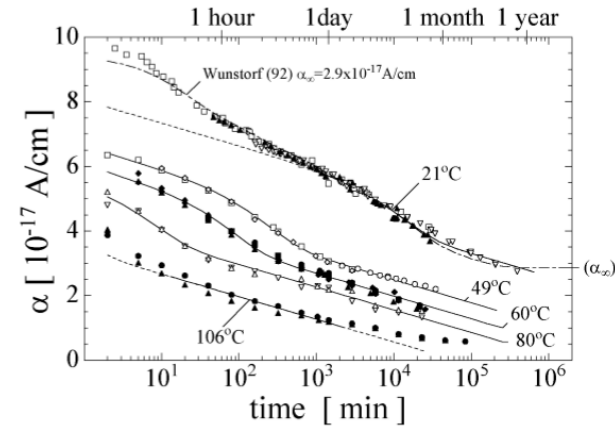
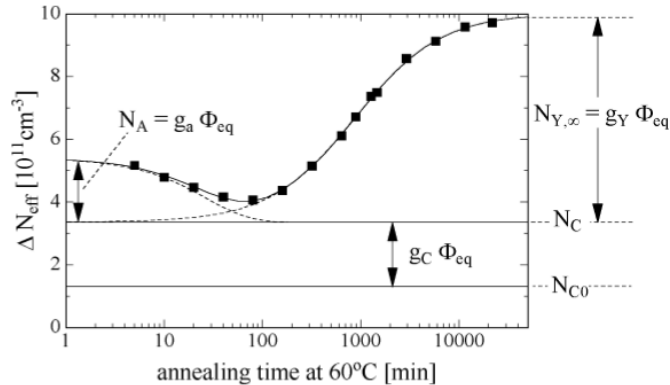
- p-type detectors, irradiated with $25 \frac{GeV}{c}$ protons at fluences between $5e13 \frac{n_{eq}}{cm^2}$ and $2e15 \frac{n_{eq}}{cm^2}$ (here up to $3e14 \frac{n_{eq}}{cm^2}$).
- One set of detectors annealed at $60^\circ C$, one set annealed at RT (ca. $23^\circ C$).

- Methods:

- Determination of the scaling factor via the trend of charge collection vs. t_{ann} .
- Determination of the effective doping concentration and its behaviour vs. t_{ann} :
 - Observation of impedance (capacitance) vs. frequency vs. voltage.
 - So far only standard analysis of capacitance vs. voltage.
- Comparison of annealing time constants with values from the literature:
 - Differences with the values from Moll thesis have been already reported, we show possible reasons.

- Theory:

- Annealing depends on time and temperature:



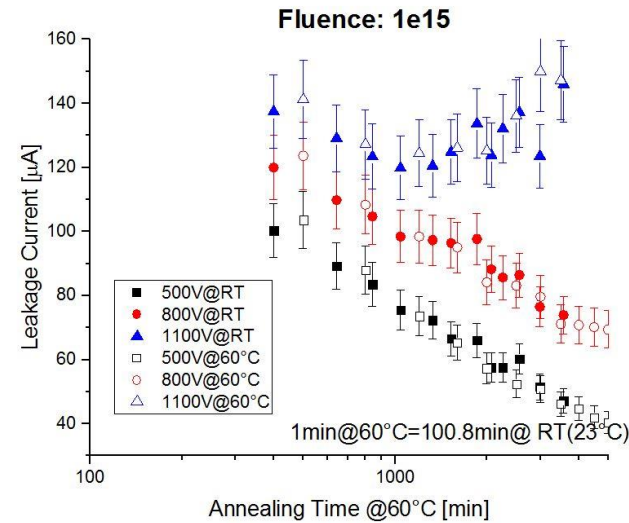
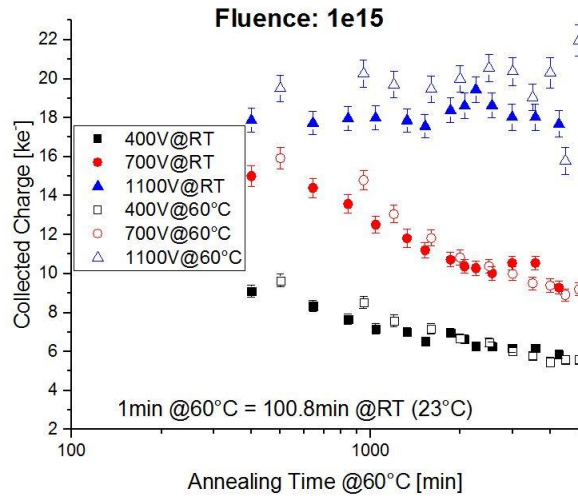
$$\Delta N_{eff} = N_0 e^{-\frac{t}{\tau}} + N_C + N_\infty (1 - e^{-kt})$$

$$\alpha(t) = \frac{\Delta I}{\Phi_{eq} V} \quad \alpha = \alpha_I e^{-\frac{t}{\tau}} + \alpha_0 - \beta \ln(t)$$

Where: $k, \frac{1}{\tau} \propto e^{-\frac{\epsilon}{k_B T}}$ [Moll]

-> faster movement of defects at higher temperatures.

- Previous results:



Fluence $\left[\frac{n_{eq}}{cm^3}\right]$	5e13	1e14	5e14	1e15	2e15
Scaling Factor k	$108 \pm 8^*$	$101 \pm 15^*$	108 ± 12	101 ± 9	108 ± 8

* determined only via leakage current trend. All Errors roughly estimated by fit accuracy.

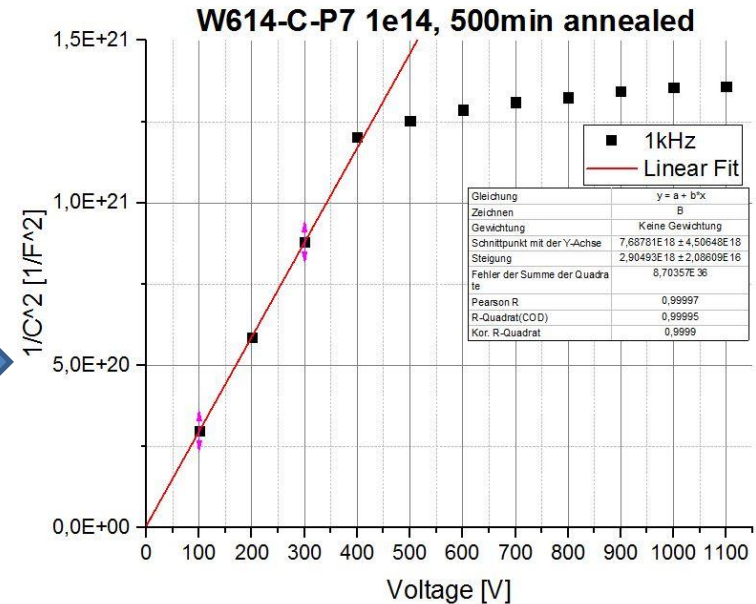
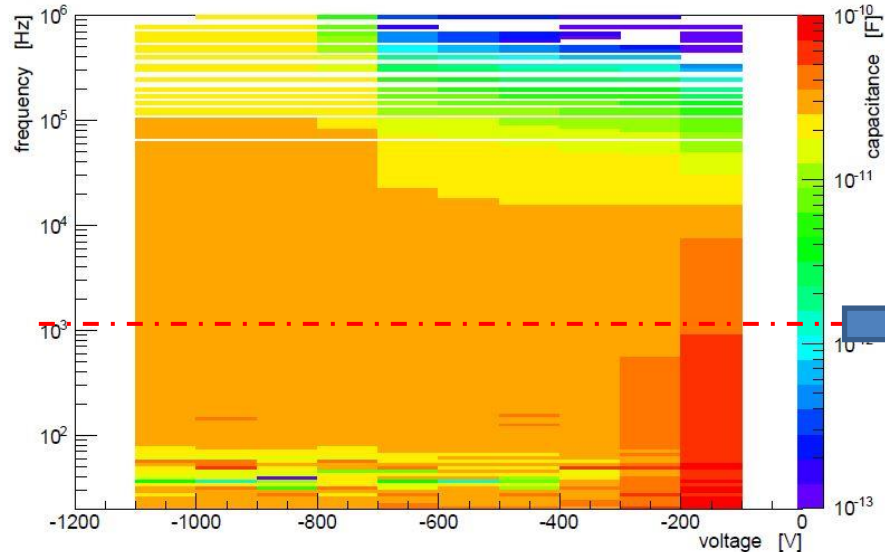
- The determined scaling factor value is 100-110 , the previously known value is around 325.

-> Is this due to different sensors? P-type vs. N-type? Different oxygen concentration?

- Effective doping concentration (N_{eff}) analysis:

Sensor: W614-C-P17, $1e14$, 500min annealed:

Capacitance vs. voltage vs. frequency

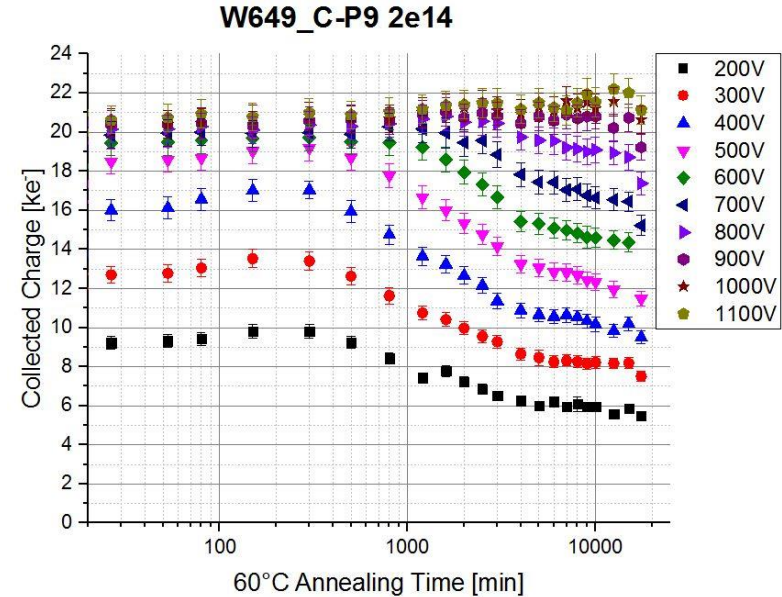
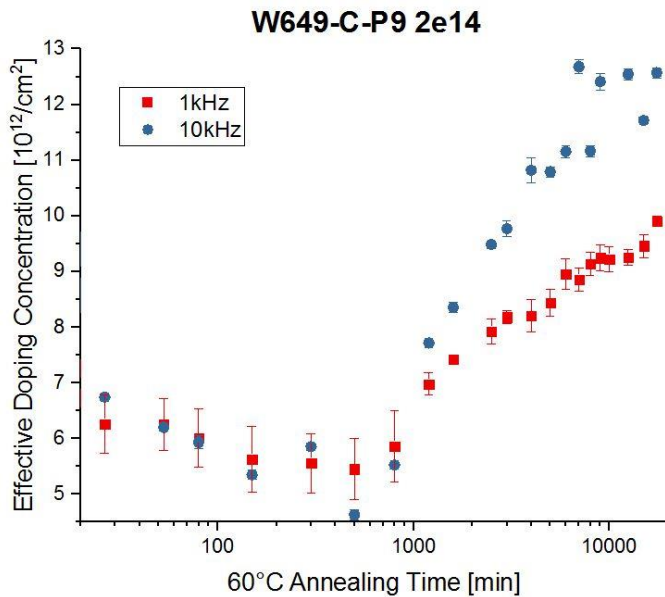


$$\frac{1}{C^2} = \frac{1}{A^2} \frac{2V}{\epsilon q N_{eff}}$$

- C-V profiles at this fluence shows clear depletion and an investigation of the effective doping concentration is still possible considering low frequencies.
- Frequency behaviour (and resistive part) will be considered especially for higher fluences.

Correlation between charge collection and effective doping concentration

- Results: $2e14 N_{eq}/cm^2$

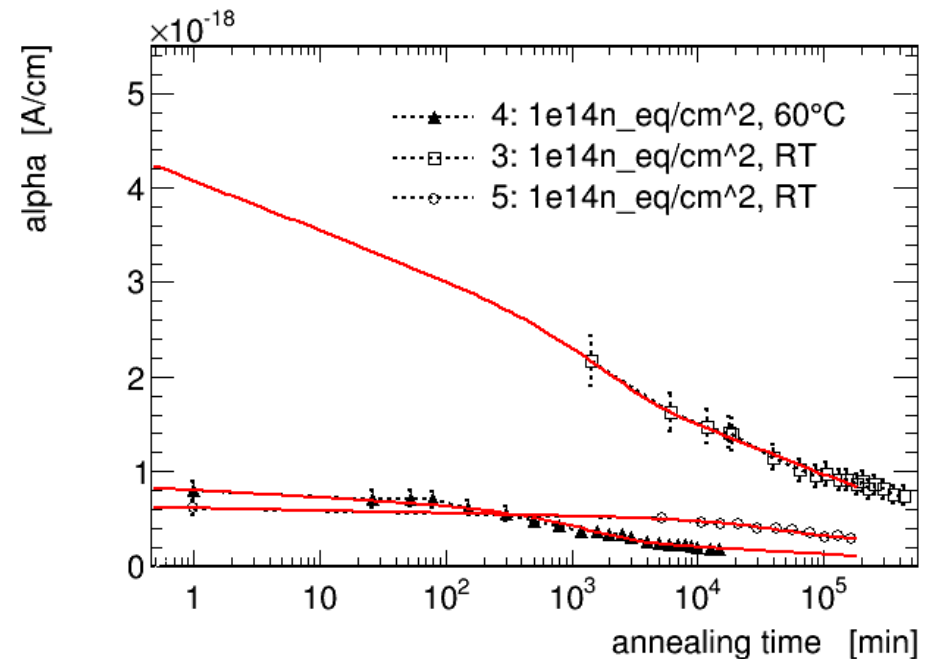
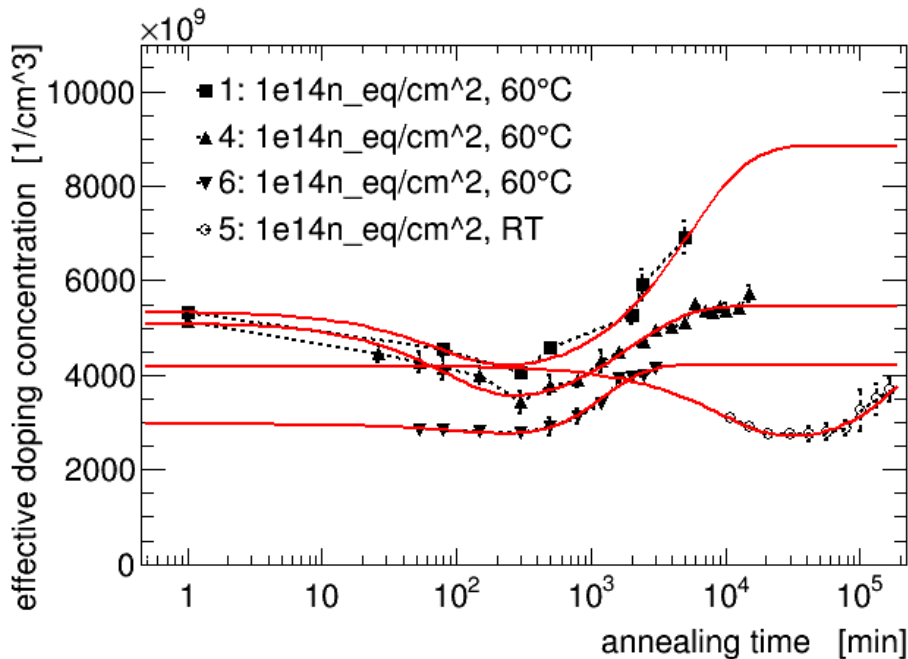


- Charge collection behaviour is correlated with the extracted effective doping concentration:
 - > Decrease of the effective doping concentration during beneficial annealing until ~300/400min, increase of it during reverse annealing (ongoing).
- Sensor lives through very long annealing times -> but fluence too low for Charge Multiplication. We are still annealing it.....

Effective doping concentration and damage parameter

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- Results: $1e14$ N_eq/cm²

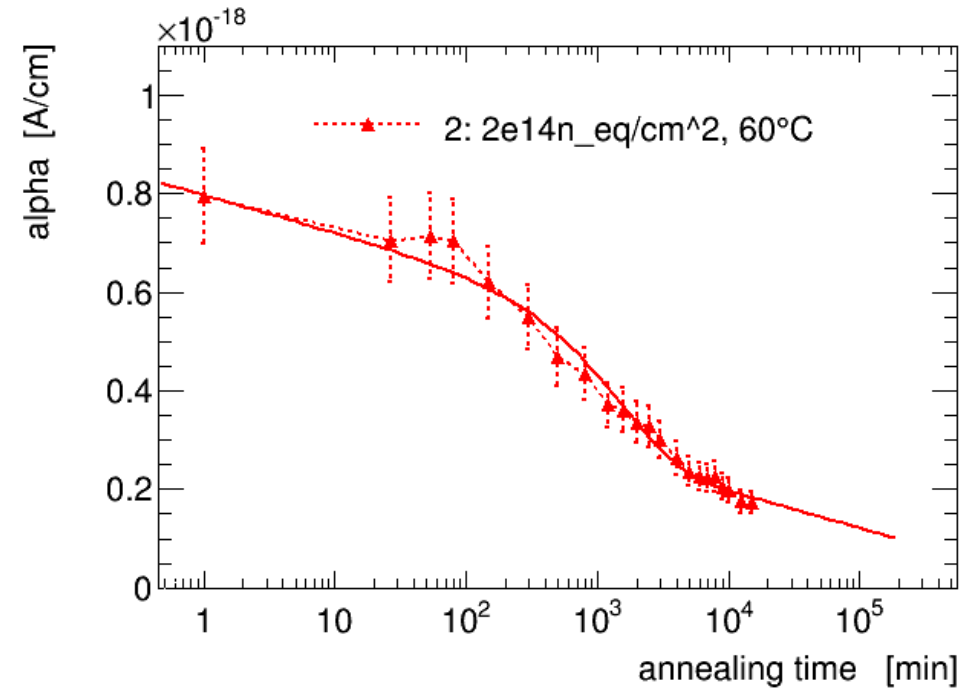
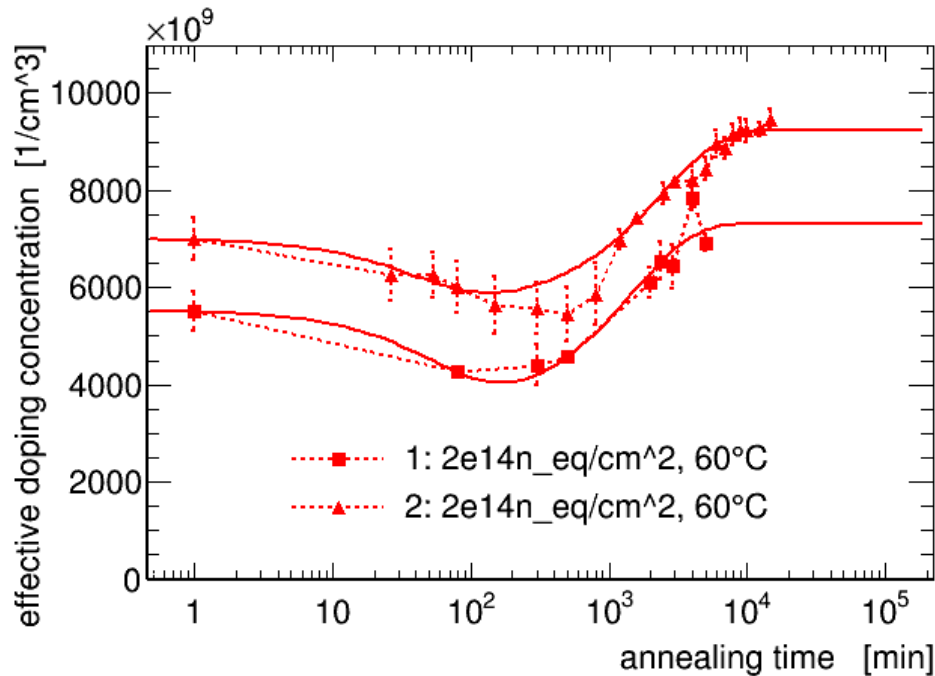


- Neff values well in the expected range:
 - at this fluence capacitance measurements are (at 1kHz) are still ok! (Capacitance is flat at low frequencies.)
- Hamburg model fits for Neff and alpha describe well the behavior.
- The beneficial annealing (minimum of Neff) appears to be 100 times slower at RT respect to 60°C....
- (sensor 3 showed larger current but similar annealing times.)

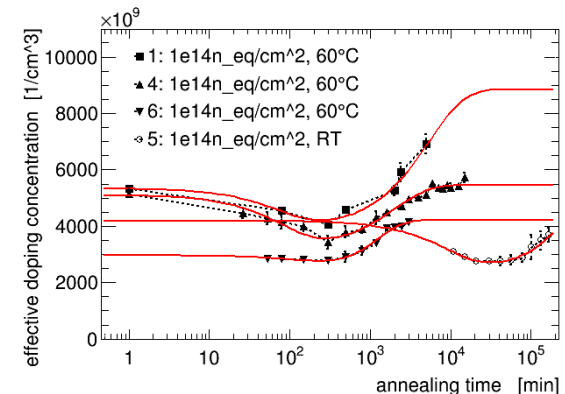
Effective doping concentration and damage parameter

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- Results: $2e14 \text{ N}_{eq}/\text{cm}^2$



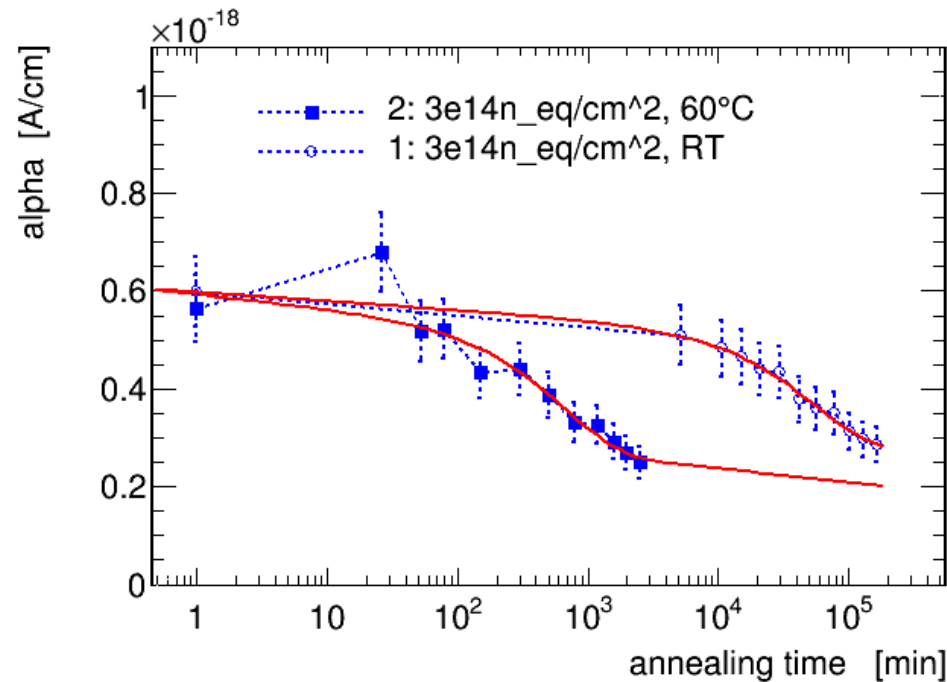
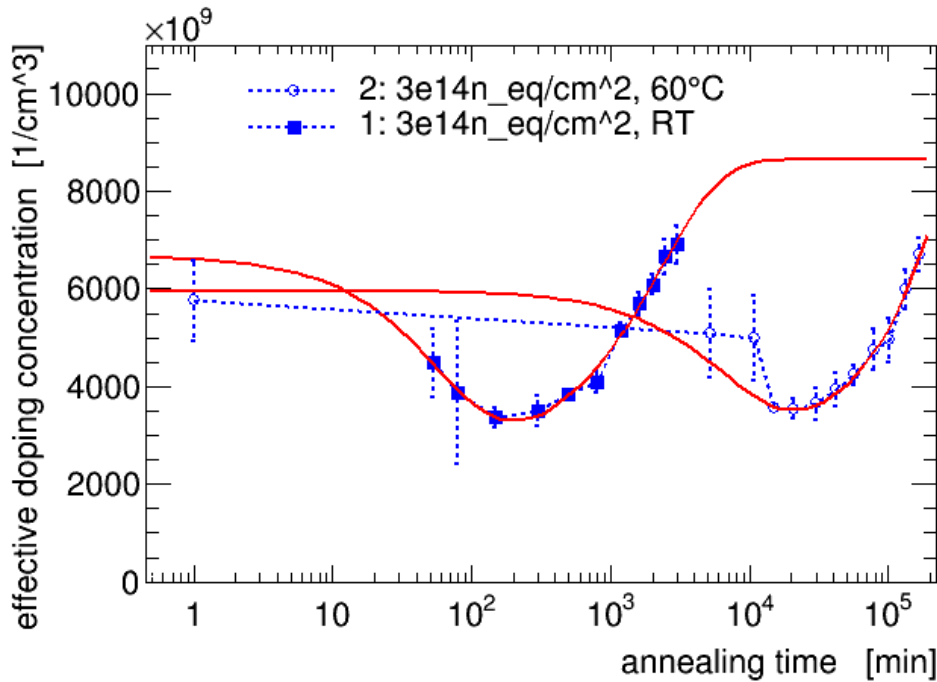
- Also at $2e14 \frac{n_{eq}}{\text{cm}^2}$ the capacitance measurements are giving reasonable results.
- Annealing time constants are similar to the ones of $1e14 \frac{n_{eq}}{\text{cm}^2}$.
- (Unfortunately we have only 60°C data for this fluence.)



Effective doping concentration and damage parameter

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- Results: $3e14 N_{eq}/cm^2$



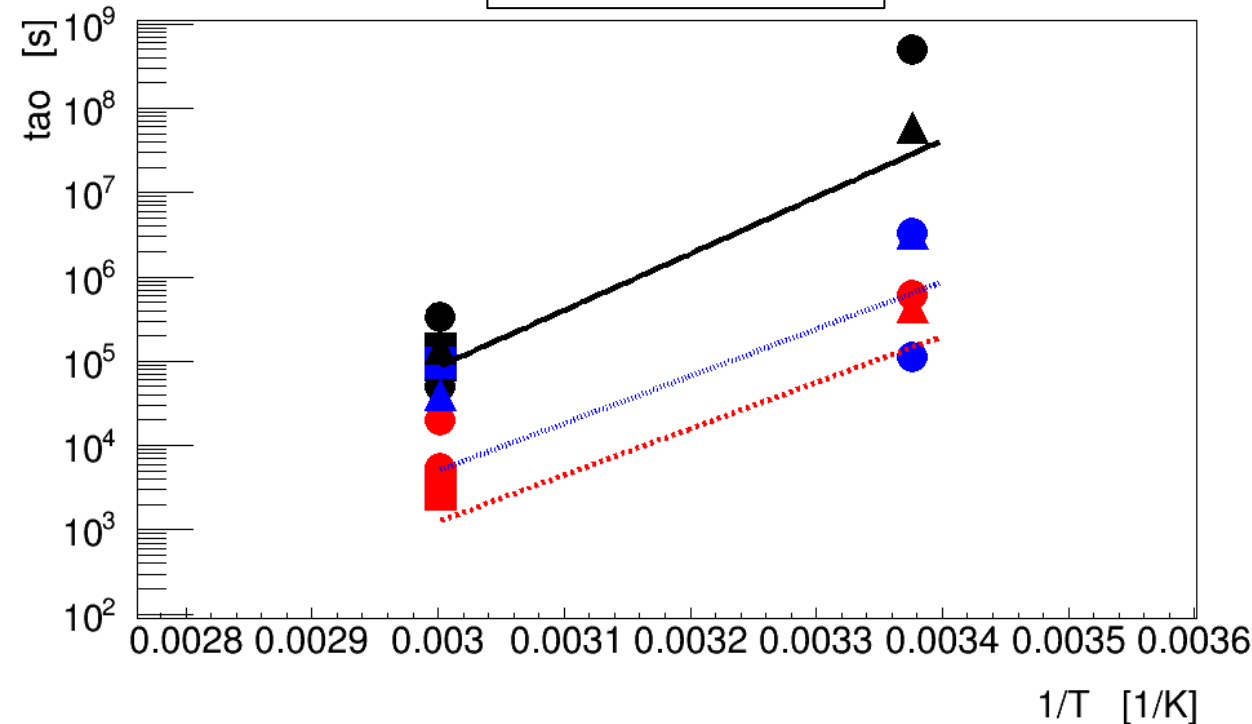
- Time constants and annealing behaviour is confirmed at $3e14 \frac{n_{eq}}{cm^2}$.
- Larger errors:
 - Capacitance measurements start to loose accuracy already at this fluence.

Investigation of the time constants

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- Result summary:

$$k, \frac{1}{\tau} = k e^{-\frac{E_a}{k_B T}}$$



- 1e14n_eq/cm2, reverse
- 1e14n_eq/cm2, beneficial
- 1e14n_eq/cm2, beneficial leakage
- 2e14n_eq/cm2, reverse
- 2e14n_eq/cm2, beneficial
- 2e14n_eq/cm2, beneficial leakage
- ▲ 3e14n_eq/cm2, reverse
- ▲ 3e14n_eq/cm2, beneficial
- ▲ 3e14n_eq/cm2, beneficial leakage
- M. Moll, reverse
- ⋯ M. Moll, beneficial
- ⋯ M. Moll, beneficial leakage

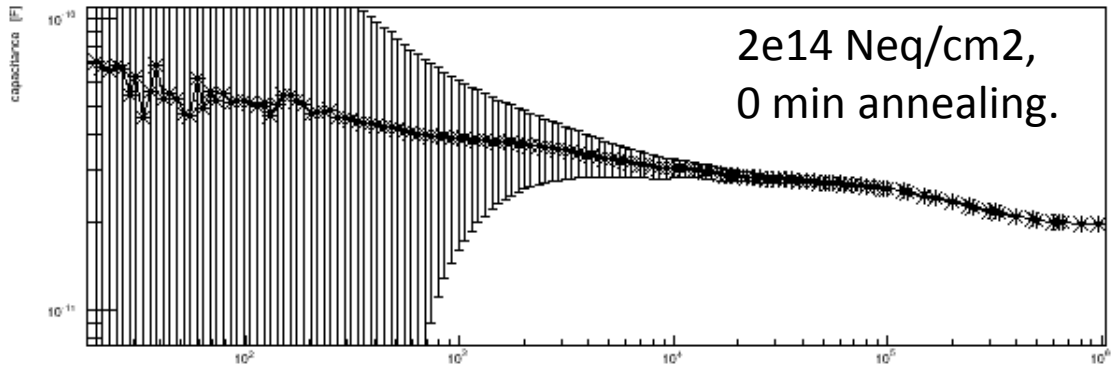
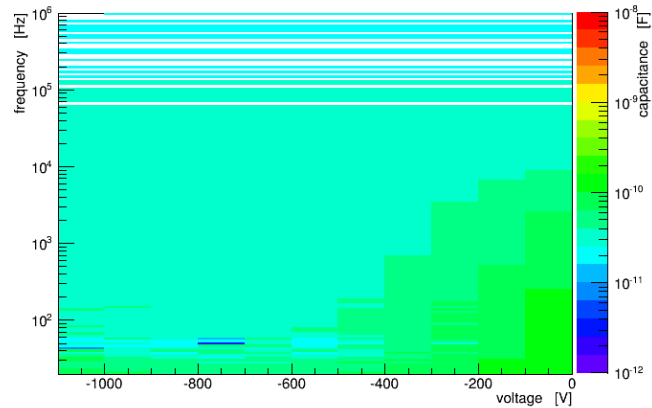
- ATLAS12 annealing generally slower.
- Some outliers for the reverse annealing (not saturating Neff): still difficult to attribute the discrepancy in the temperature factor to the activation energy (slope).
- Significant difference in the frequency factor (offset), especially for beneficial annealing:
 - ATLAS12 having a lower annealing frequency => lower than the phonon frequency for a single jump $\sim 1e13 s^{-1}$, maybe indicating a long range migration.

Impedance measurements: work in progress

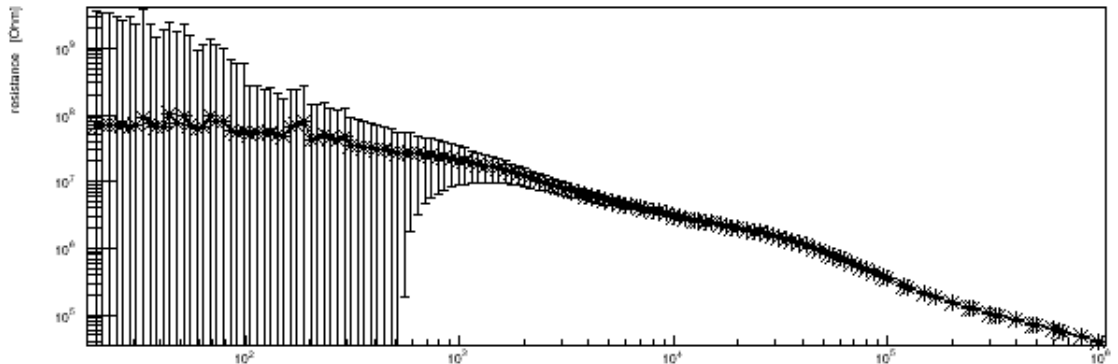
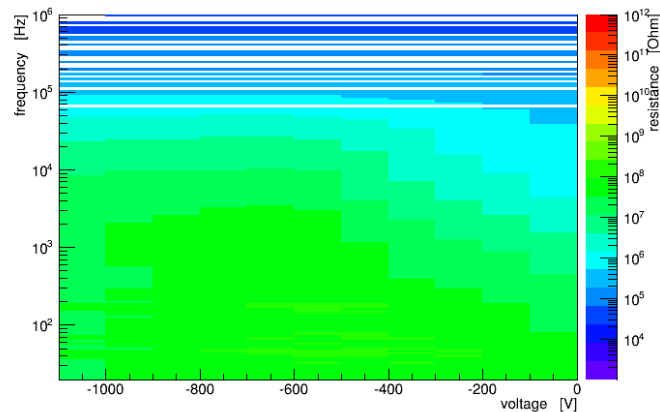
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- **Discussion:**
- If from one side the frequency behaviour is a limit for the Neff studies, from the other it offers a perspective on the defect behaviour:
 - This will be studied versus annealing....

Capacitance vs. voltage vs. frequency



Resistance vs. voltage vs. frequency



- Resistance change in frequency as well as the capacitance:
 - Due to defect reaction times.

- **Discussion:**
- The determined effective doping concentration fits in the expected range and behaves like expected with increasing annealing time.
- The trend corresponds (inverted) to the trend of the collected charge.
- The discrepancies with previously studied (mainly n-type) sensors show that ATLAS12 sensors anneal generally slower; difference mainly in annealing frequency of the beneficial annealing.
 - A deeper understanding could come from defect spectroscopy.
- ATLAS12 sensors can live through very long annealing times without charge multiplication or breakdown, if the fluences are not too high. We are still annealing them....
- In the future we want to use impedance/ capacitance measurements also to investigate defects more, especially how they change during annealing.

Thank you for your attention!

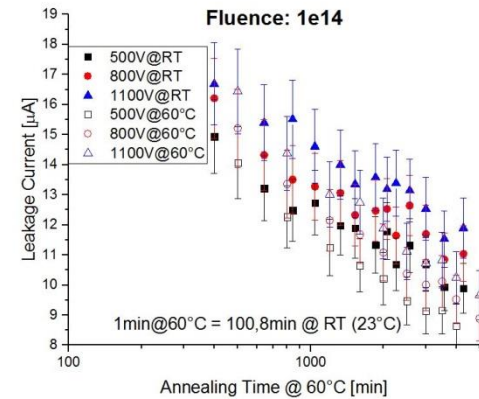
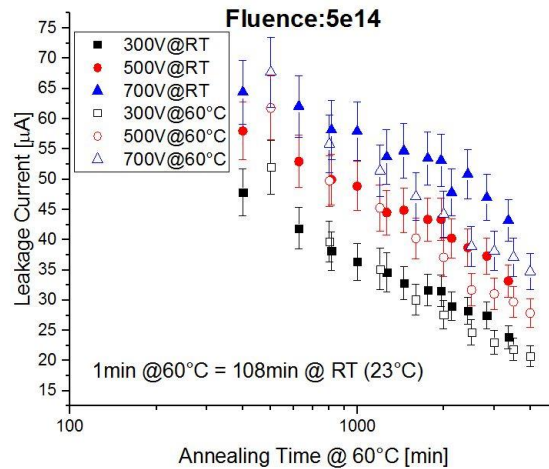
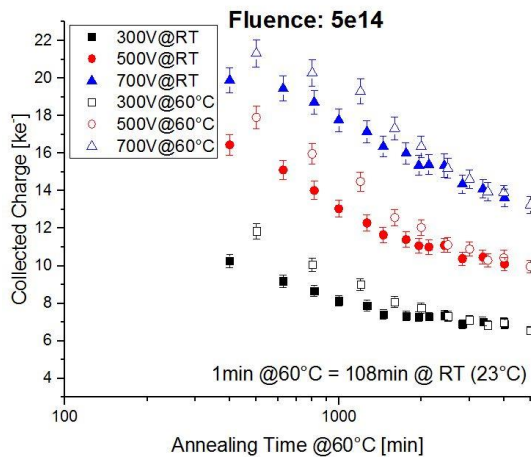
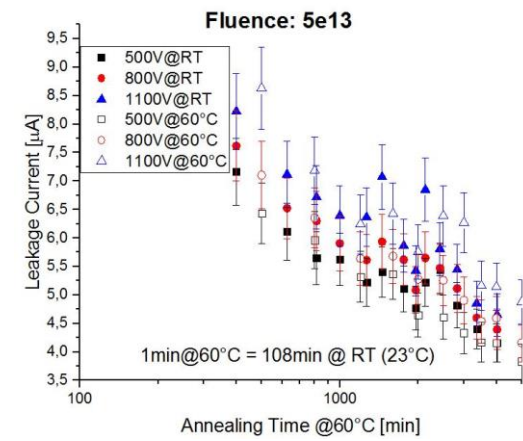
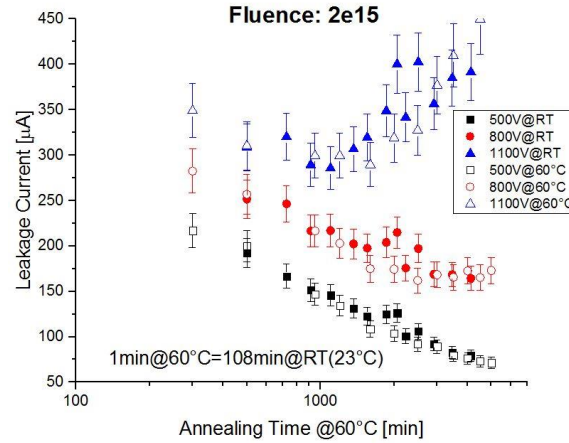
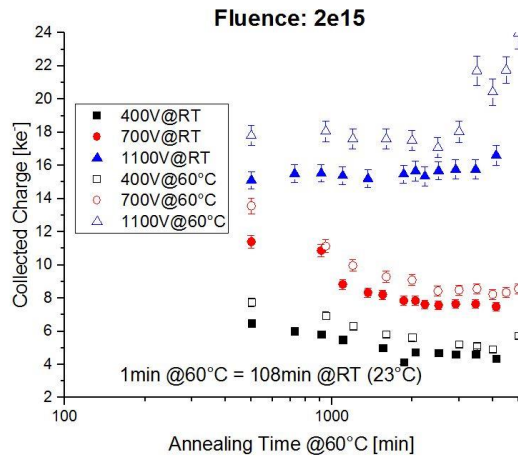
... and a special thanks to Riccardo Mori for a lot of time and effort!

Backup: Factor

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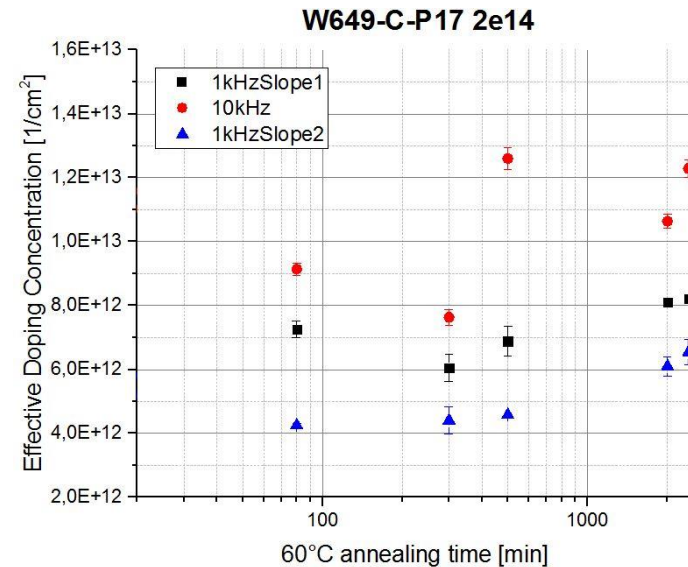
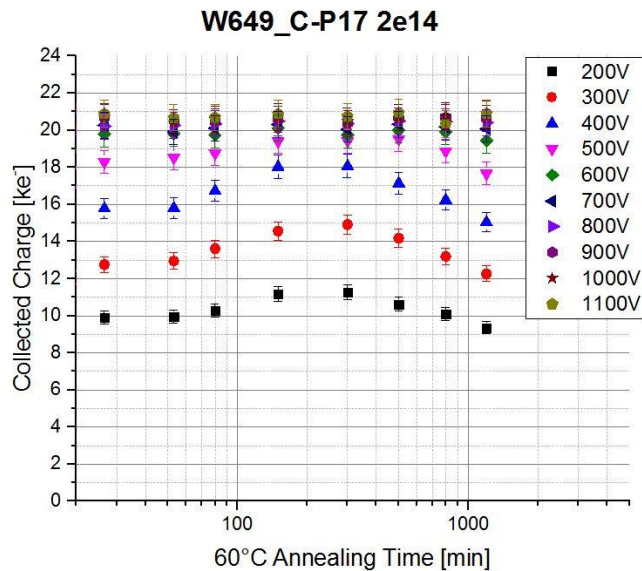
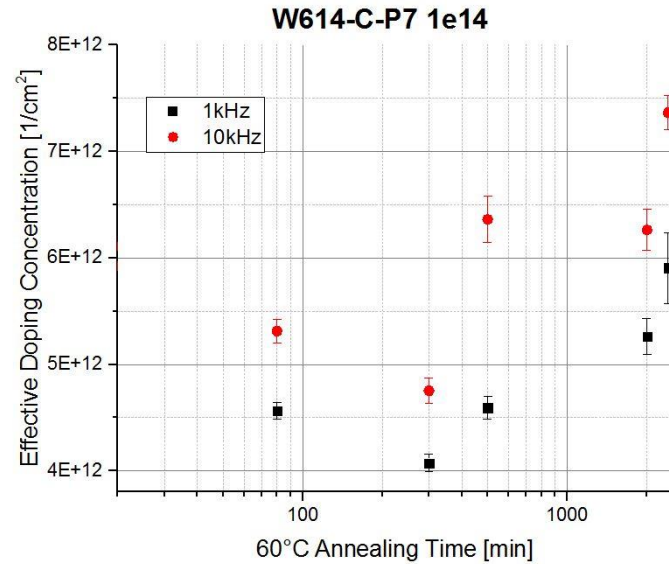
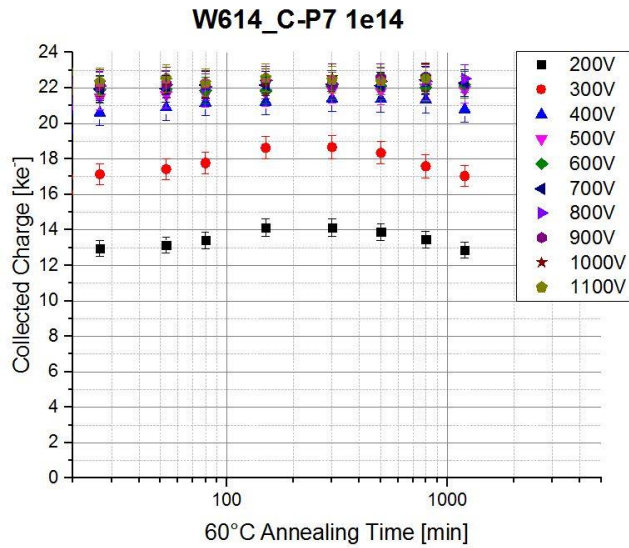


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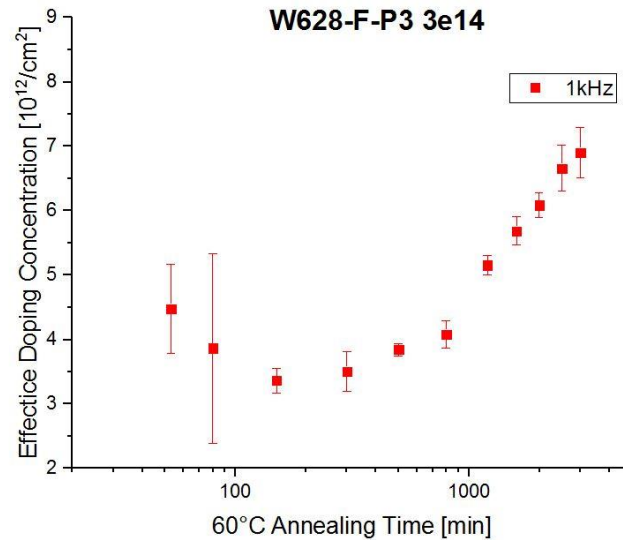
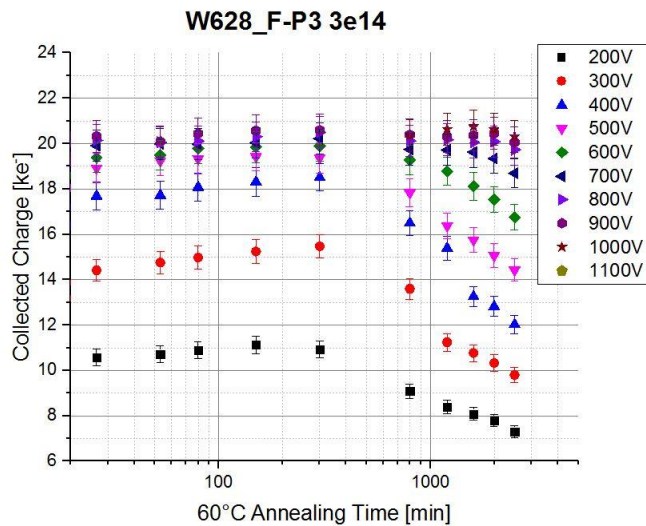
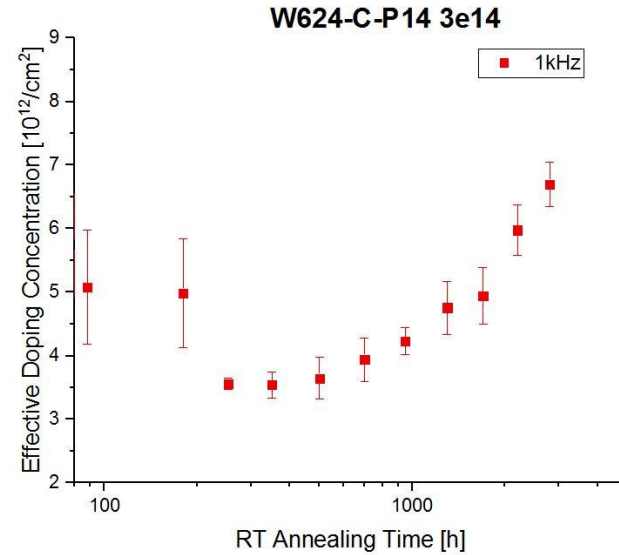
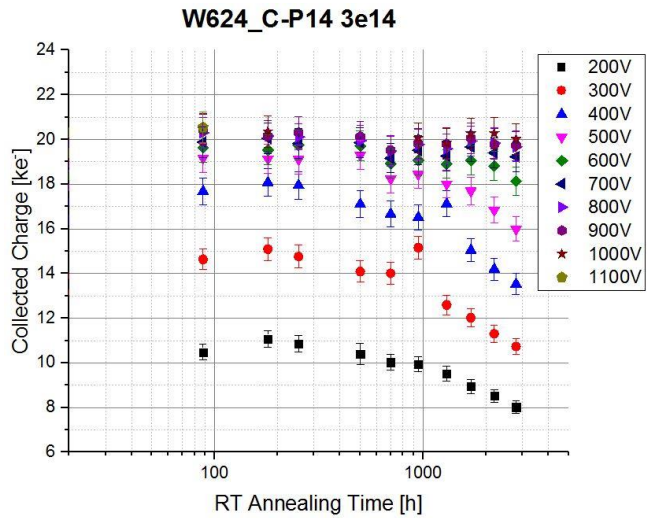
Backup: Effective doping concentration

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